



# HIGH RESOLUTION X-RAY IMAGING SENSOR WITH SOI CMOS TECHNOLOGY

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# Outline

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- II. Design of INTPIX4
  - i. Specifications
  - ii. Circuit
  - iii. DAQ System
- III. Device Performance Tests
  - i. Noise Measurement & Effect of CDS Circuit
  - ii. Energy Resolution
  - iii. Spatial Resolution
- IV. Summary

# Introduction of the SOI Pixel Detector

- A monolithic pixel detector with Silicon-On-Insulator (SOI) CMOS Technology -> 0.2  $\mu\text{m}$  fully-depleted (FD) - SOI pixel process
  - SOI Pixel Detector (SOIPIX) : Processed by OKI Semi. Co. Ltd.

## SOIPIX Advantages

- **No mechanical bump bonding**
  - > High Density, Low material budget
  - > Low Parasitic Capacitance, High Sensitivity
- **Standard CMOS circuits can be built**
- **Based on Industrial standard technology**

Circuit Layer :  $\sim 40$  nm

Buried Oxide (BOX) Layer : 200 nm

Sensor Layer : 100 - 725  $\mu\text{m}$

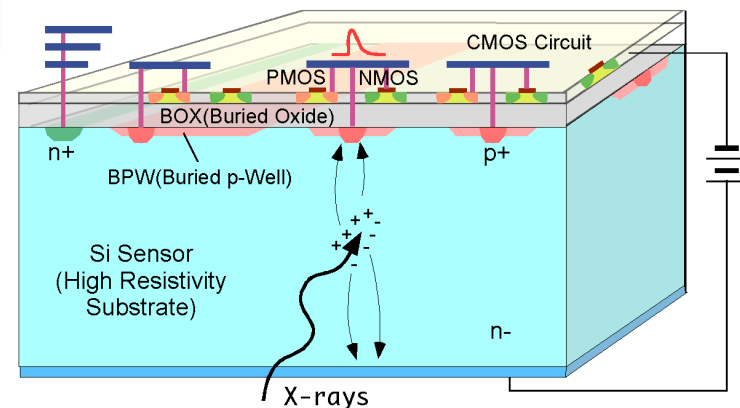
## More details

-> Dr. Miyoshi's talk (Mon 13, 14:20)

## SOI Pixel Process

New Process to make pixel detector with SOI technology. Joint development with OKI Semi. Co. Ltd.

SOI Pixel Detector



Cross section of the SOI Pixel Detector

# INTPIX4 Specifications

- Integration Type SOIPIX Detector
- Chip Area : 10.3 x 15.5 mm<sup>2</sup> (Effective Area : 8.7 x 14.1 mm<sup>2</sup>)
- Number of Pixels : 512 x 832 (= 425, 984)
- Pixel Size : 17 x 17 μm<sup>2</sup>
- Correlate Double Sampling (CDS) Circuit in each pixel.
- 13 Analog Out
- Sensor thinned to 260 μm
- Sensor Wafer Type
  - Czochralski (CZ) - SOI : 700 Ω cm
  - Floating Zone (FZ) - SOI : 7 kΩ cm
- **Fully-depleted by FZ-SOI wafer**
- **Back-illumination**

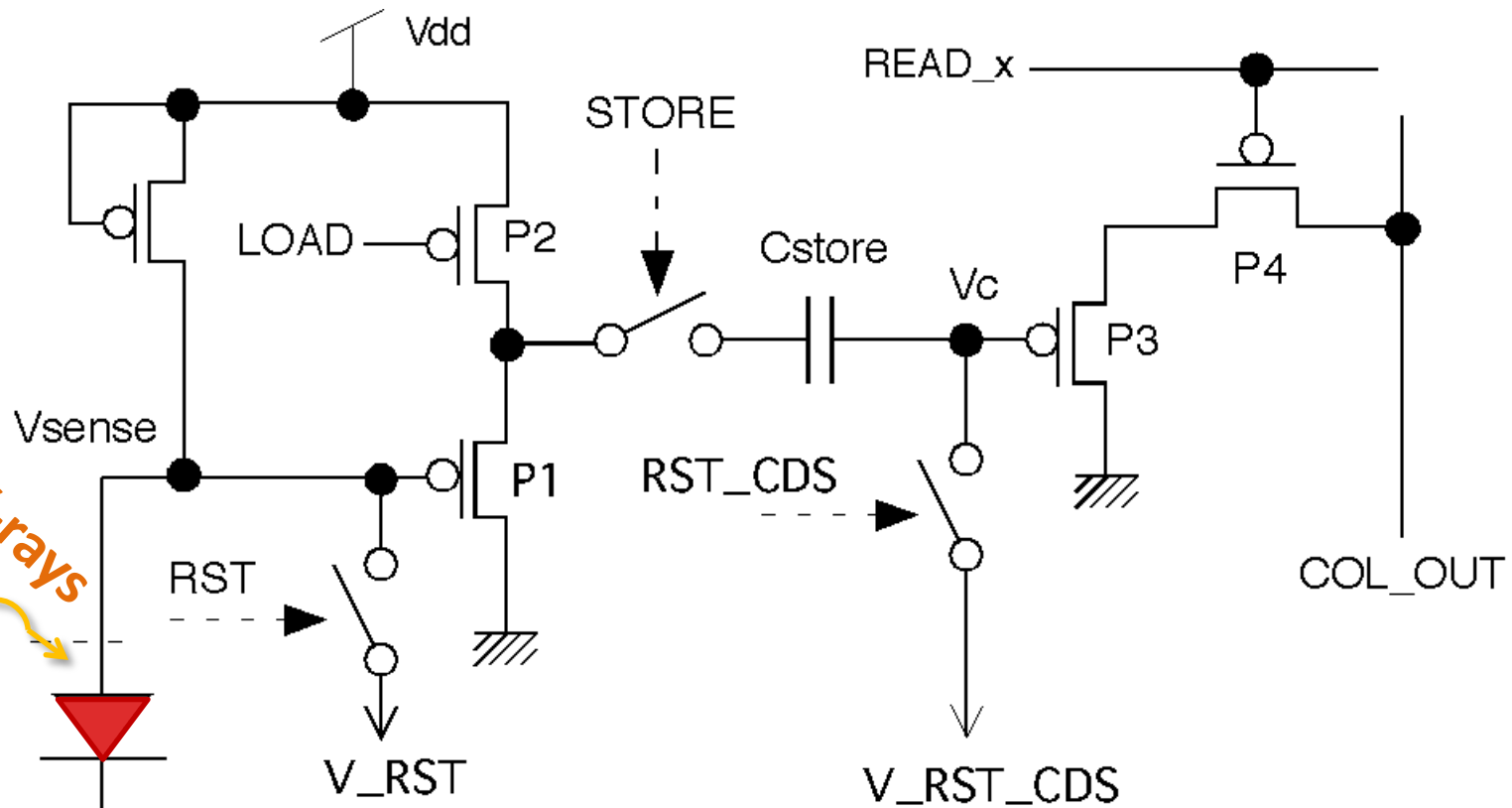


15.5 mm  
INTPIX4 Chip Photo

This presentation treat only CZ-SOI wafer.

# INTPIX4 Circuit

- CDS Circuit : CDS Cap.  $\rightarrow$  Cstore, Reset Tr.  $\rightarrow$  RST & RST\_CDS
- Stored Signal read out from COL\_OUT.

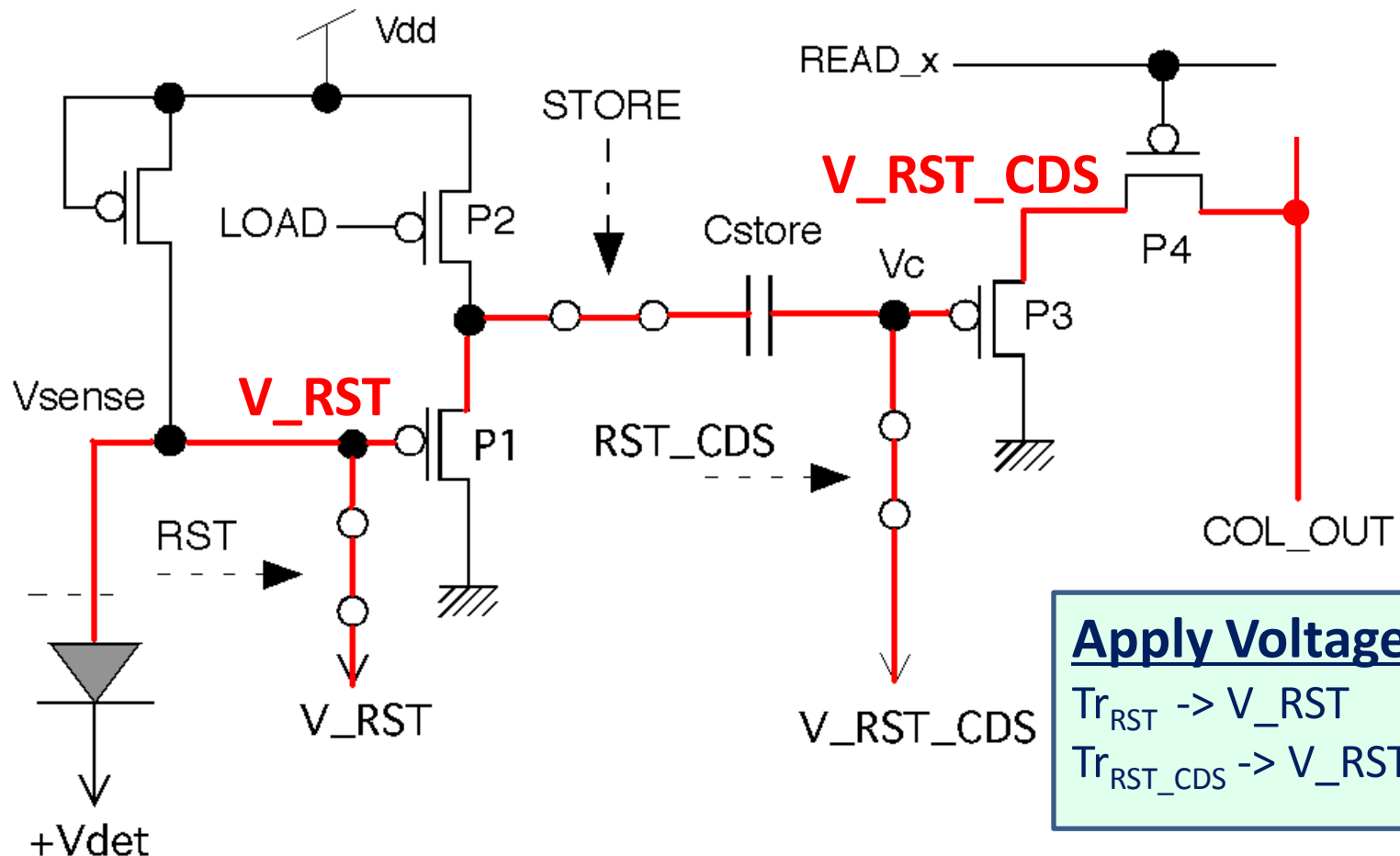


**1 pixel circuit of the INTPIX4**

# How to Suppress Reset Noise

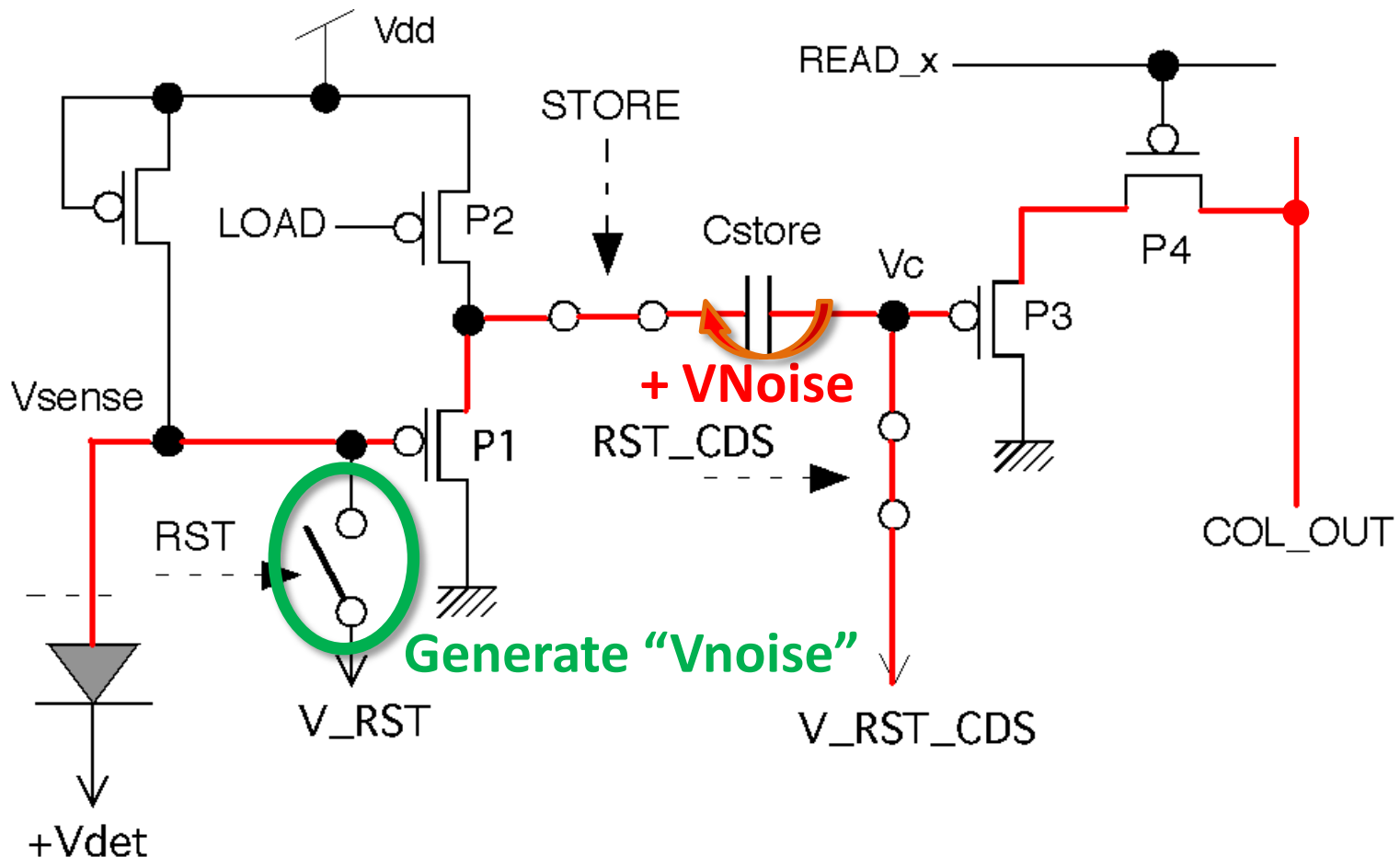
## 1. Reset state.

- Apply voltage to each reset Tr (RST & RST\_CDS).



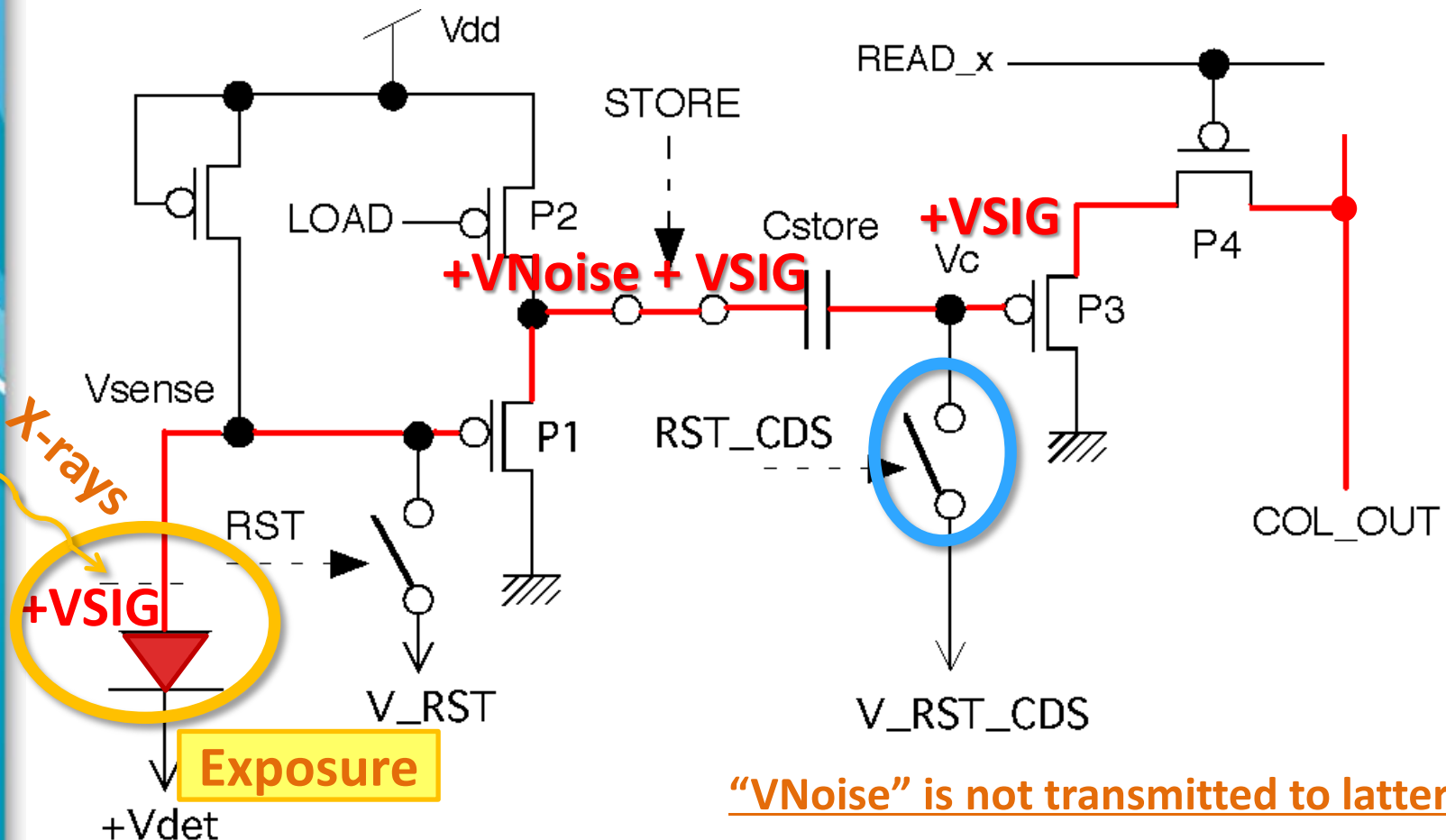
# How to Suppress Reset Noise

2.  $Tr_{RST}$  is turned off, and noise is generated (  $V_{Noise}$  :  $kTC$  noise). It is kept the CDS Capacitor ( $C_{store}$ ).



# How to Suppress Reset Noise

- $Tr_{RST\_CDS}$  is turned off, and exposure of signal (VSIG).  
The signal is added in the circuit.

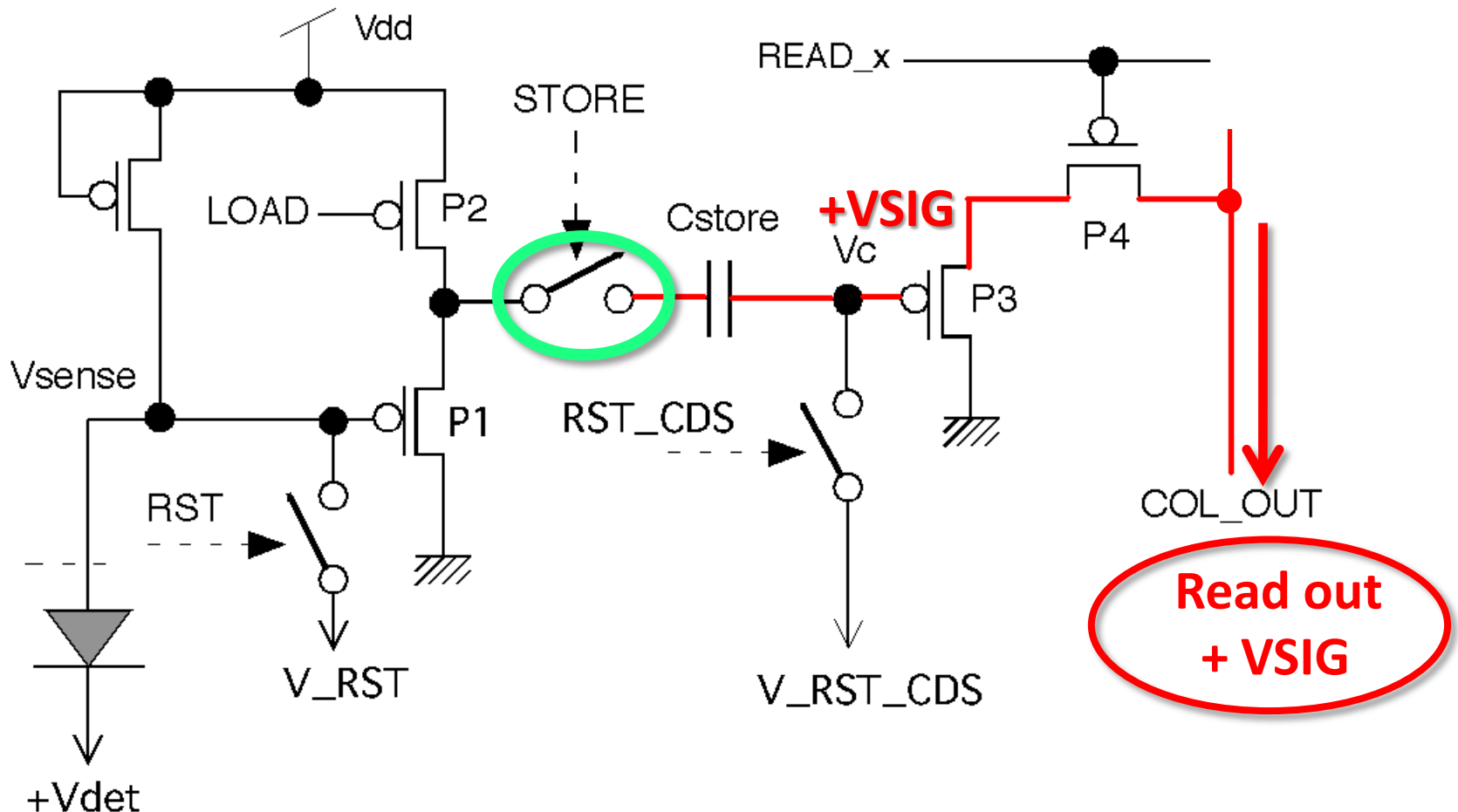


"VNoise" is not transmitted to latter part.



# How to Suppress Reset Noise

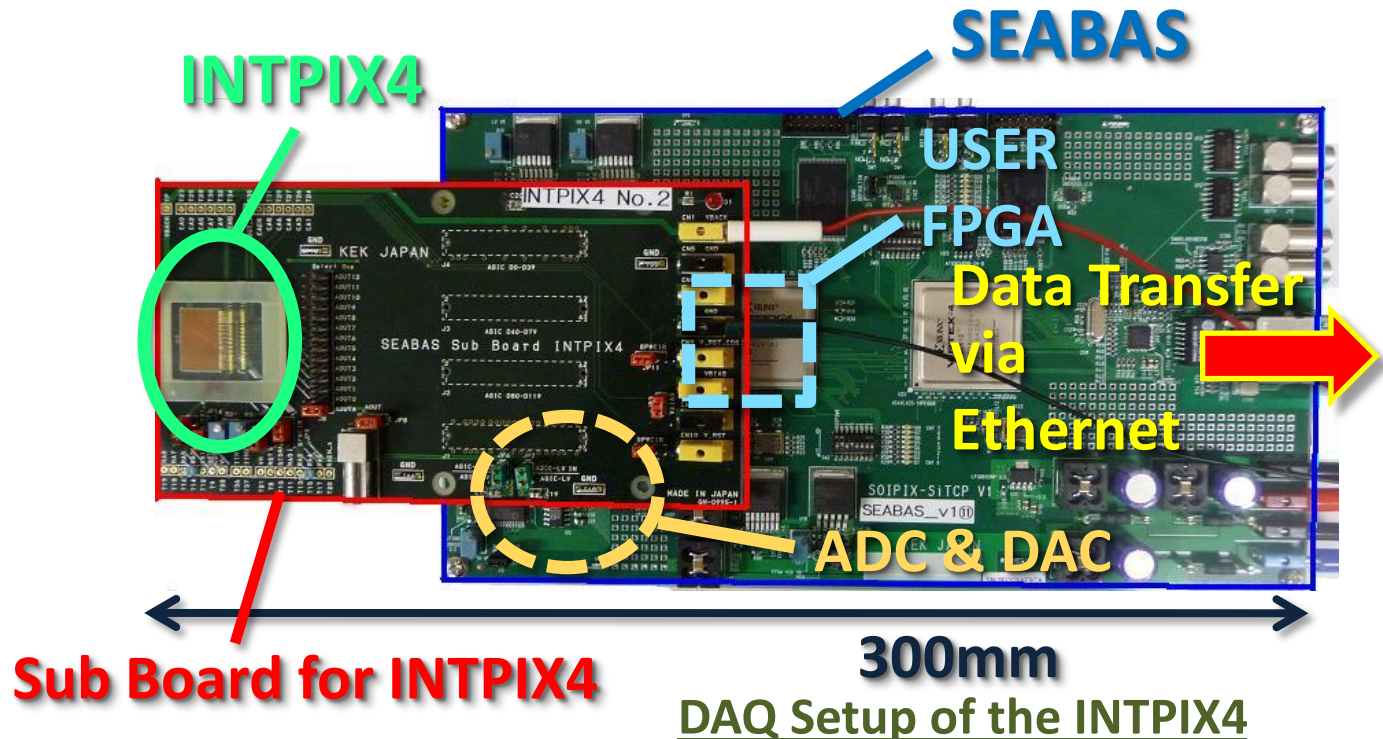
- After integration time,  $Tr_{STORE}$  is turned off. Then the voltage of the  $V_c$  node is read out from "COL\_OUT". The  $V_{Noise}$  will not appear in the read out voltage.



# DAQ System

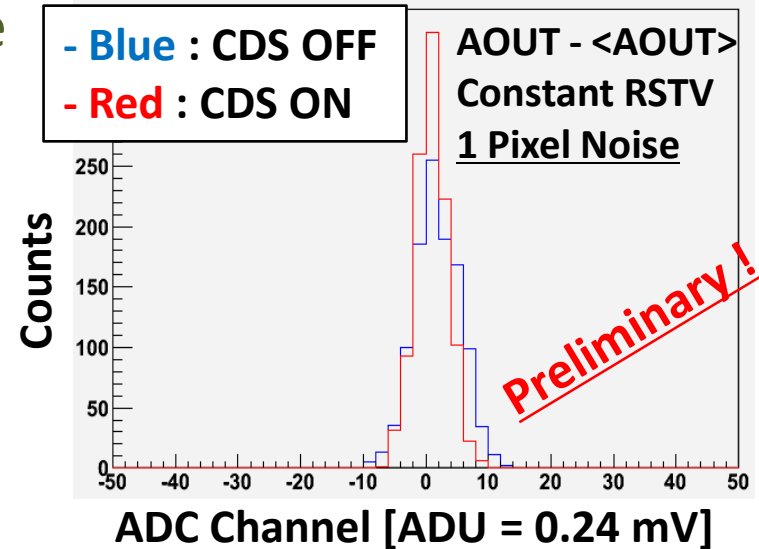
- SoI EvAluation Board with Sitcp (SEABAS)
- General data read out board for SOIPIX.
- A FPGA controls the SOI Pixel chip.
- Directly transferred to Ethernet.

Power Supply :  $\pm 5$  V  
Clock : 25 MHz  
Network : 100 Mbps  
ADC, DAC,  
NIM IN x2, NIM OUTx 2



# Noise Measurement & Effect of CDS Circuit

- Noise Measurement with 1 pixel @ 7 °C.
- Comparison with measured noise and calculated kTC noise.
- The CDS circuit is working as expected.



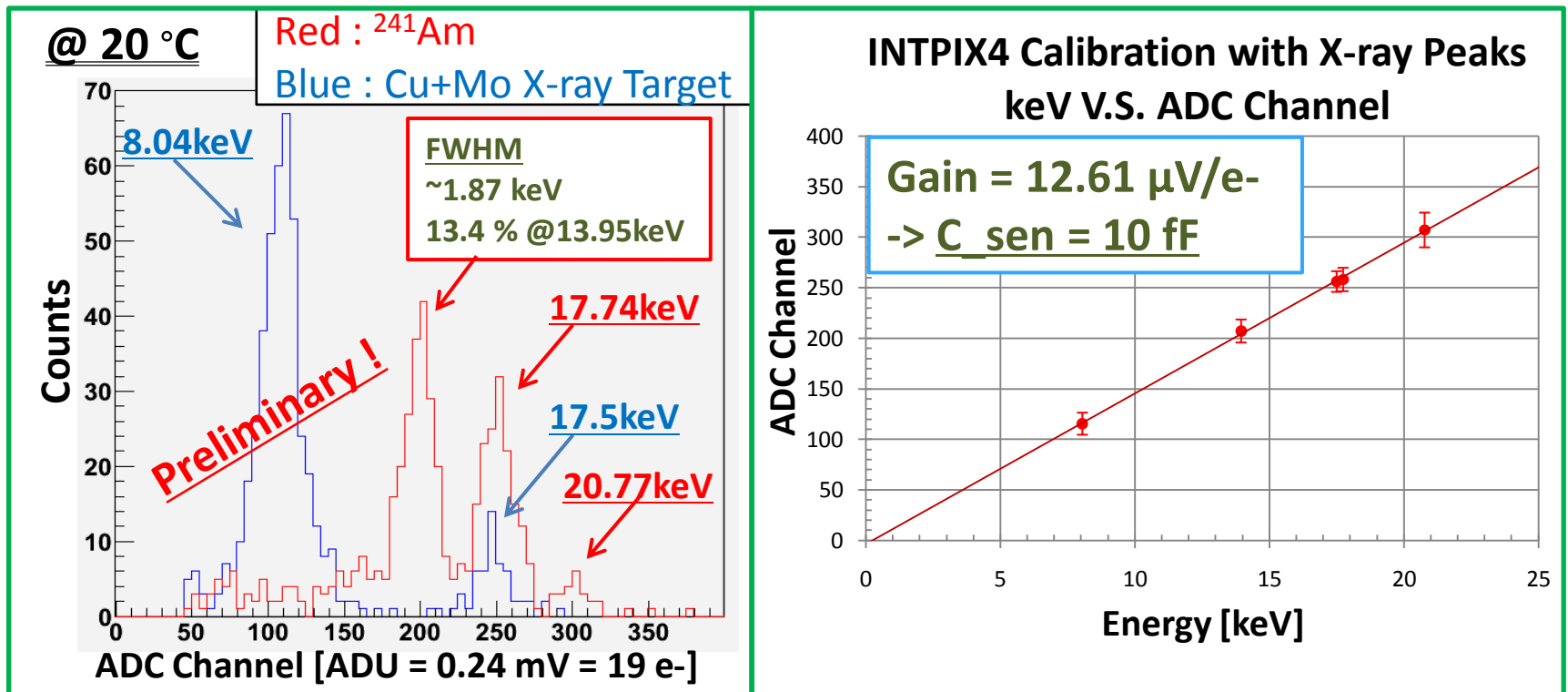
**@ 7 °C (280 K)**

Measured Noise (RMS)		Measured Noise ( $\Delta \text{RMS}^2$ )	Calculated kTC Noise
CDS OFF	CDS ON		
70 e-	49 e-	$(70^2 - 49^2)^{1/2} = 50 \text{ e-}$	$(kT@280 \text{ K} / 10 \text{ fF}) = 49 \text{ e-}$

# Energy Resolution

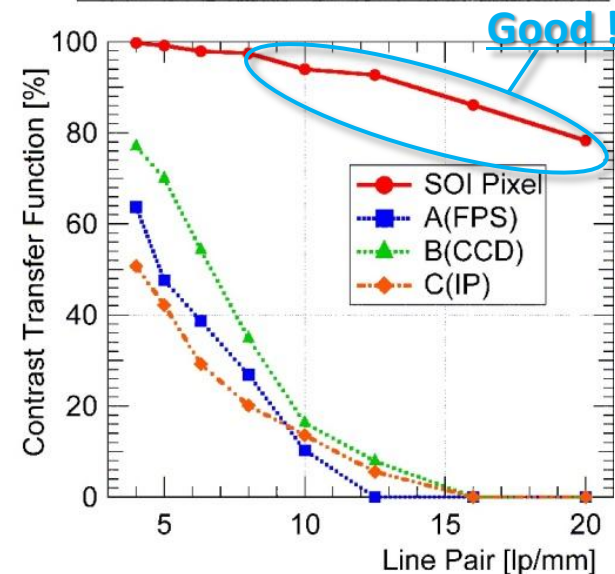
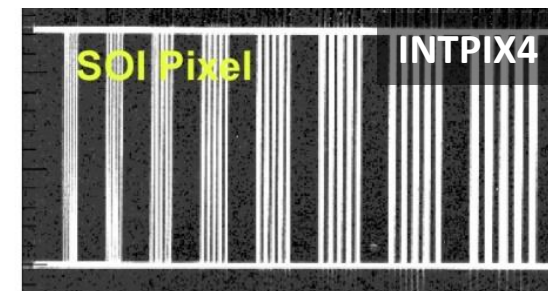
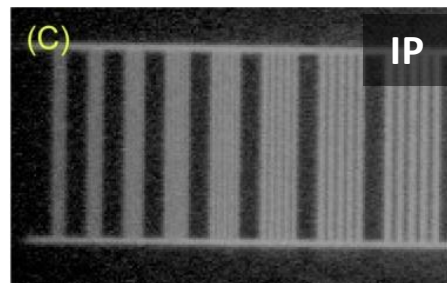
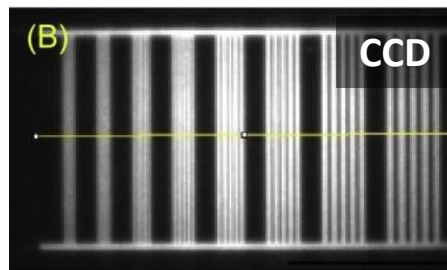
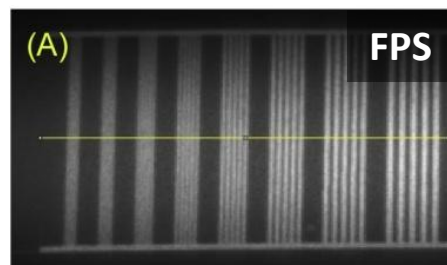
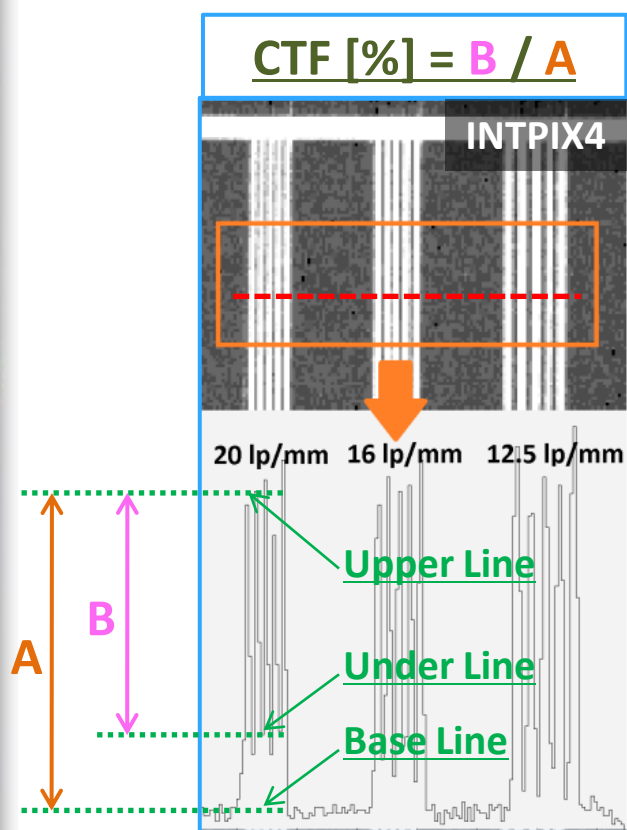
- Energy Spectrum @Room Temp.
  - $^{241}\text{Am}$  and Cu + Mo X-ray Target
- **FWHM : 13.4 % @ 13.95 keV**
- **Sensor Capacitor : 10 fF**

V sensor = 200 V  
Integration Time = 250  $\mu\text{s}$   
Back-illumination



# Spatial Resolution

- Comparison of contrasts with commercial X-ray devices.
  - SOI Pixel : INTPIX4, Flat Panel Sensor (FPS), CCD, and Imaging Plate (IP)
- **INTPIX4 shows very good spatial resolution !**



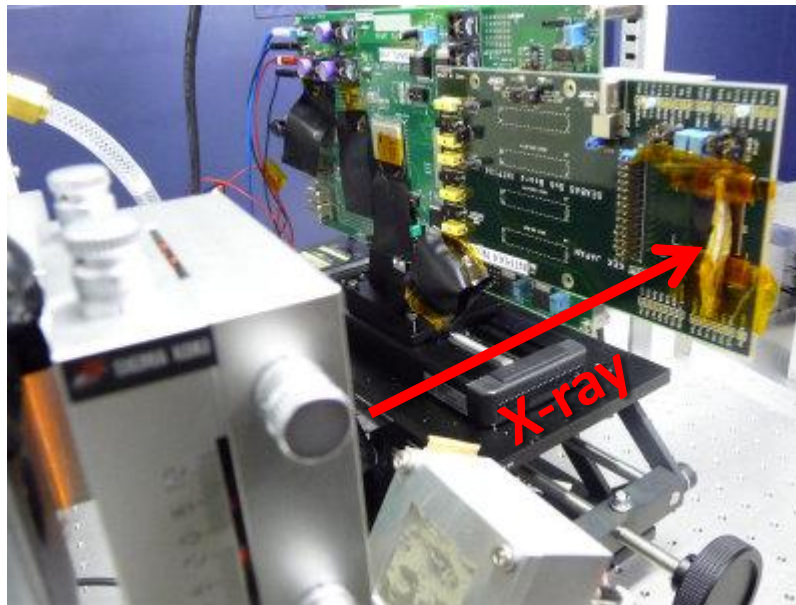
**Contrast Transfer Function**

# INTPIX4 X-ray Imaging

- X-ray Imaging @ Room Temp.
- Niboshi (Japanese) : a small dried sardine

V sensor = 200 V

X-ray Tube : Mo, 20 kV, 5 mA



Setup for X-ray imaging taken by an INTPIX4 .

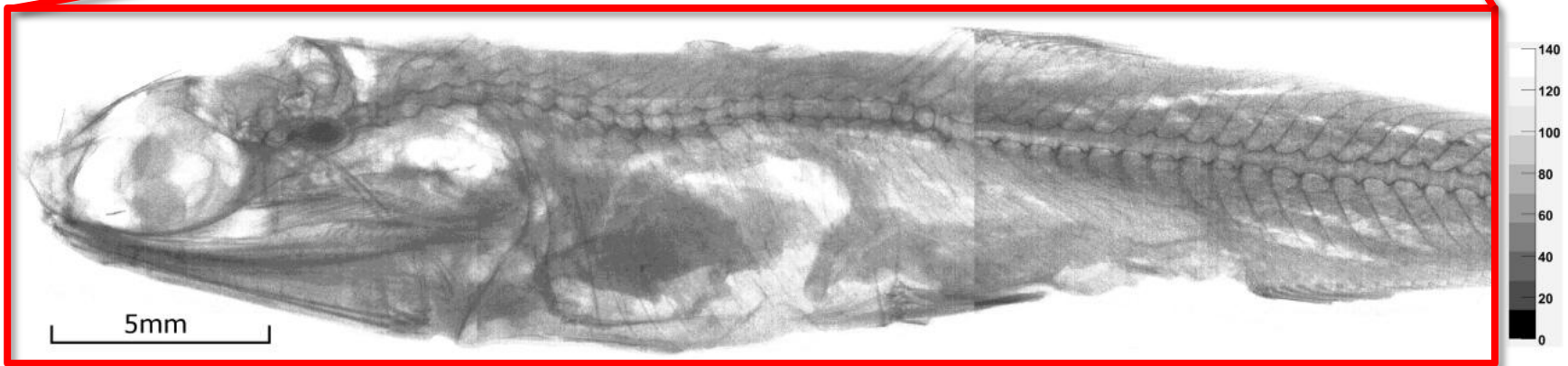
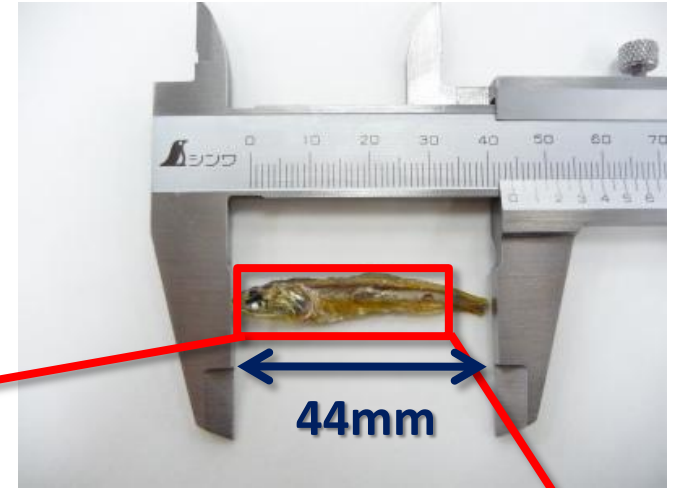
# INTPIX4 X-ray Imaging

- Fine Resolution & High Contrast !

250  $\mu$ s Int. x 500 fr

\* It is clear even by 100 fr.

\*\* It depends on the number of photons.



X-ray Imaging of a small dried sardine taken by an INTPIX4 (3 images are combined).

# Summary

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- We have developed a monolithic pixel detector with a 0.2  $\mu\text{m}$  FD - SOI CMOS technology.
- The Integration-type SOIPIX worked successfully.
  - INTPIX4 : 17  $\mu\text{m}^2$ , 426 k pixels

## INTPIX4

- Energy Resolution -> FWHM 13.4 % @ 14 keV.
- Sensor capacitor is 10 fF.
- The CDS circuit is operated successfully. (kTC noise suppress)
- INTPIX4 shows very good spatial resolution.
  - CTF : 78 % @ 20 lp/mm.
- We succeeded in acquiring the clear X-ray image @ Room Temp.

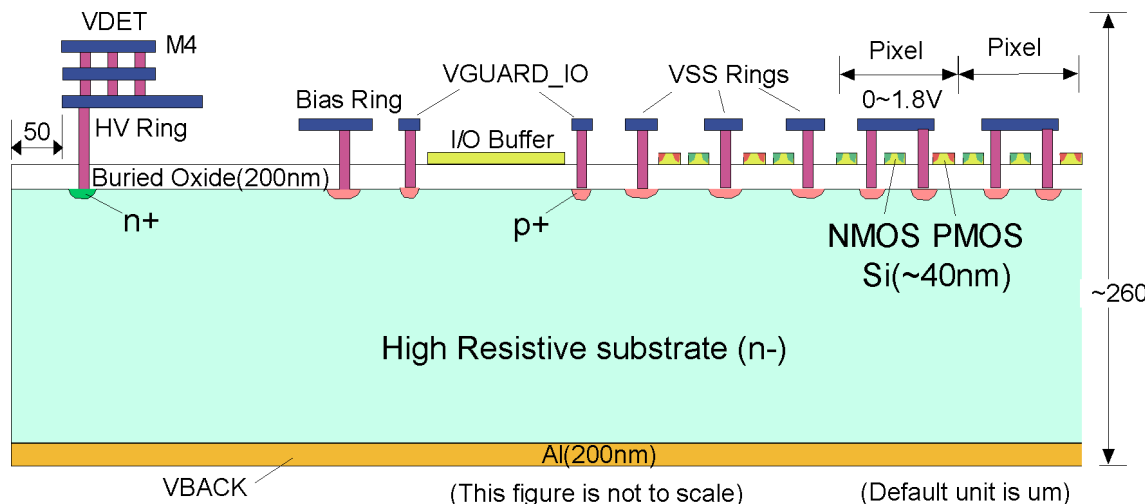




# BACKUP

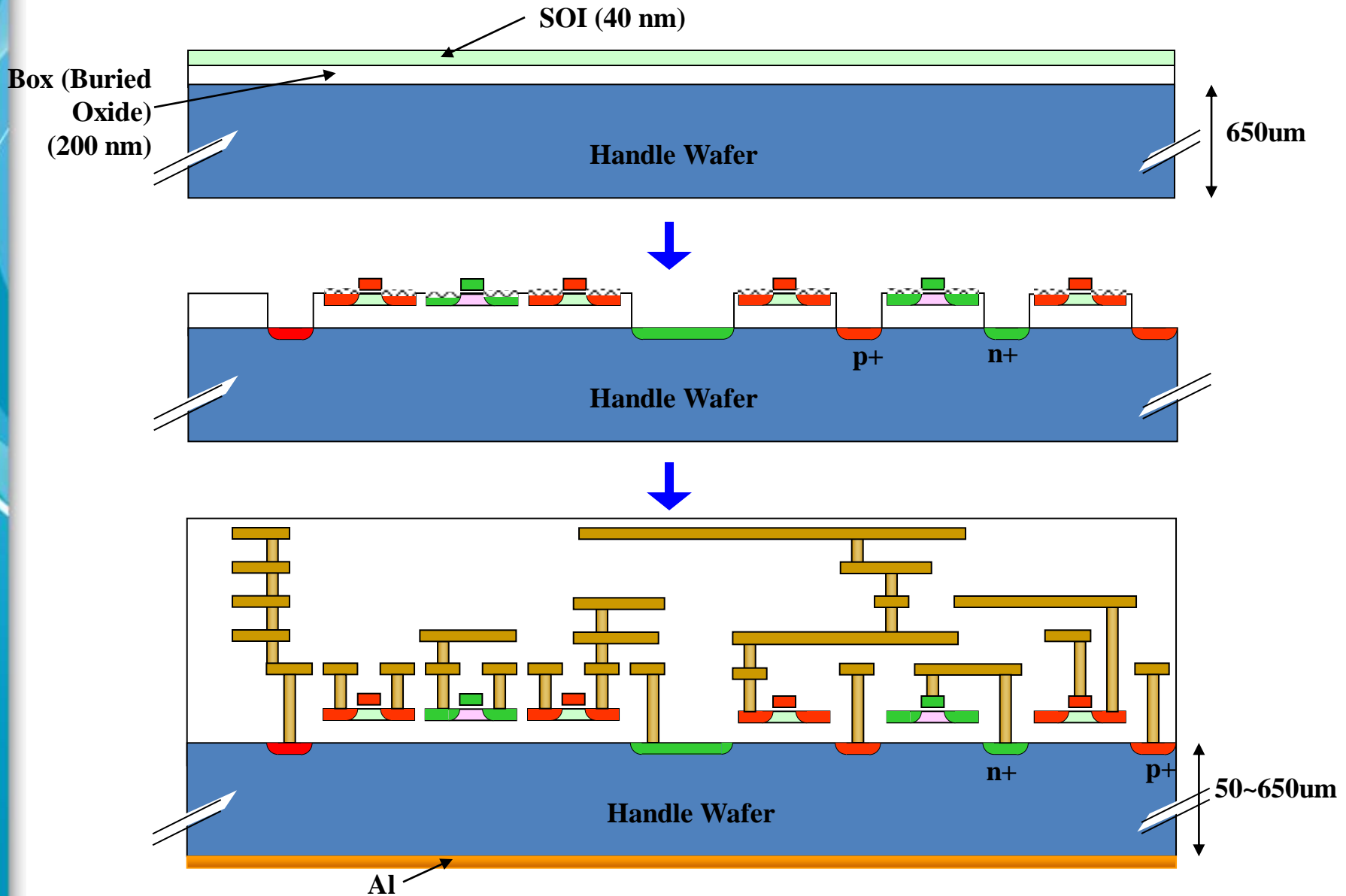
# OKI 0.2 $\mu\text{m}$ FD-SOI Pixel Process

Process	0.2 $\mu\text{m}$ Low-Leakage Fully-Depleted SOI CMOS (OKI) 1 Poly, 4 (5) Metal layers, MIM Capacitor, DMOS option Core (I/O) Voltage = 1.8 (3.3) V
SOI wafer	Diameter: 200 mm $\phi$ , Top Si : Cz, $\sim 18 \Omega\text{-cm}$ , p-type, $\sim 40 \text{ nm}$ thick Buried Oxide: 200 nm thick Handle wafer: Cz $\sim 700 \Omega\text{-cm}$ ( <i>n-type</i> ), 650 $\mu\text{m}$ thick
Backside	Thinned to 260 $\mu\text{m}$ and sputtered with Al (200 nm).



An example of a SOI Pixel cross section

# SOI Pixel Process Flow



# Comparison of Spatial Resolution

- INTPIX4 was compared with commercial X-ray devices :

## X-ray Flat Panel Sensor (FPS)

Specification:

CMOS APS

Scintillator : CsI

Effective area : 52.8 x 52.8 mm<sup>2</sup>

# of pixels : 1032 x 1032

Pixel size : 50 μm<sup>□</sup>

RMS noise : 80 e-

Minimum exposure time : ~ 0.4 sec

Full well : 450000 e- / pixel

Effective Dynamic Range : ~ 14 bit

Frame rate : 3 fps

14 bit digital output

Application : X-ray diffraction

## Fiber-coupling X-ray CCD

Specification:

Fiber-coupling CCD 3.57 : 1

Scintillator : Gadox

# of pixels : 1392 x 1040

Effective Pixel size : ~ 24 μm<sup>□</sup>

RMS noise : 3.5 ADU

Minimum exposure time : ~ 30 msec

Full well : 225000 e- / pixel

Effective Dynamic Range : ~ 14 bit

16 bit full image with fusion made @ 20 MHz

Application : Phase-contrast imaging, etc ...

# Comparison of Spatial Resolution

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- INTPIX4 was compared with commercial X-ray devices :

## Imaging Plate (IP)

### Specification:

Photostimulatable phosphor (PHP) Plate

Effective area : 20 x 25 cm<sup>2</sup> (Reusable)

Pixel size : 50 μm<sup>□</sup> / 100 μm<sup>□</sup> / 200 μm<sup>□</sup>

RMS noise : 65,536 / 256

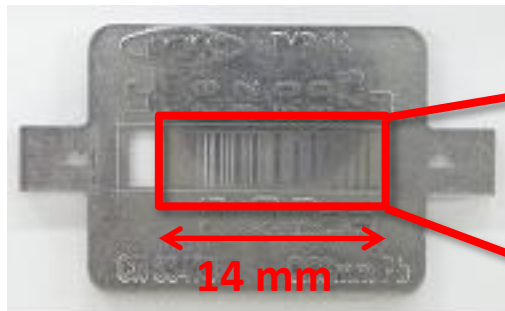
Effective Dynamic Range : 4 digit / 5 digit

Sensitivity : S = 1,000 / 4,000 / 10,000 / 30,000

Readout time : ~5min.

# X-ray Chart Pattern

This is a X-ray Chart Pattern Type.14



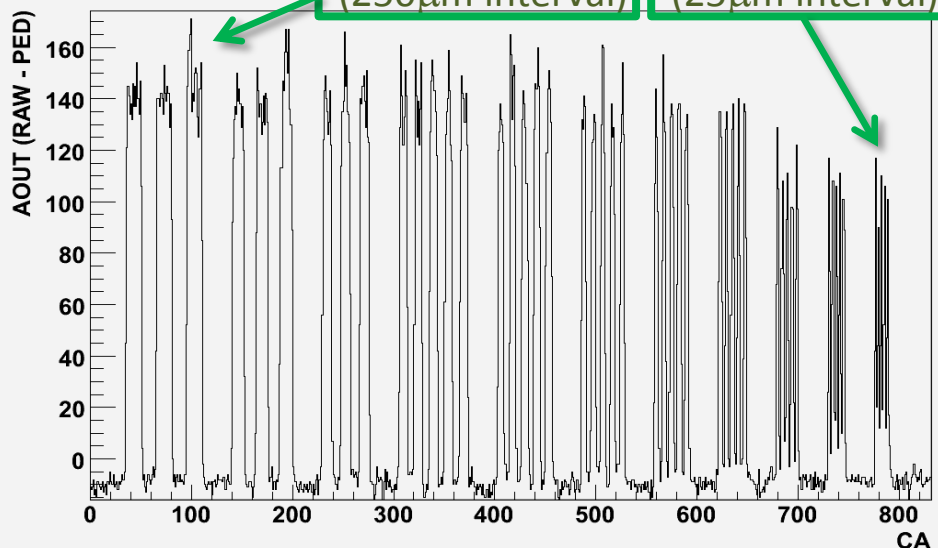
RA : 300



INTPIX4 RA(300) Cut

2 lp/mm  
(250 $\mu$ m interval)

20 lp/mm  
(25 $\mu$ m interval)



From the left

2.0, 2.5, 3.2, 4.0, 5.0, 6.3, 8.0,  
10.0, 12.5, 16, 20 [lp / mm]

\* lp : Line Pairs